

In the Claims:

Please cancel claims 2, 5, 8-10, and 13-14. Please amend claims 3-4, 6, 11, and 15.

Please add new claims 29-35. The claims are as follows:

1. (Original) An integrated circuit, comprising:

a predefined block of functional circuitry having a plurality of I/O pins; and
a backside I/O pad electrically connected to each I/O pin through a backside via of the
integrated circuit.

2. (Canceled)

3. (Currently amended) The integrated circuit of claim 1, wherein said I/O pins are formed in a
lowest interconnect level of an the integrated circuit chip.

4. (Currently amended) The integrated circuit of claim 1, wherein said integrated circuit is
fabricated using backside via is formed in a bulk silicon substrate or using a silicon-on-insulator
substrate of the integrated circuit.

5. (Canceled)

6. (Currently amended) The integrated circuit of claim [[5]] 1, wherein said predefined block of
functional circuitry includes a first portion containing functional circuitry and a second portion

containing said I/O pins, and wherein said backside vias connect to said I/O pins in said second portion.

7. (Original) The integrated circuit of claim 1, further including:

a plurality of frontside I/O pads; and
additional I/O pins, each additional I/O pin electrically connected to one frontside I/O pad
of the integrated circuit by a global wiring connection.

8-10. (Canceled)

11. (Currently amended) A method of making electrical connection to an integrated circuit,
comprising:

providing a predefined block of functional circuitry having a plurality of I/O pins; and
connecting a backside I/O pad of the integrated circuit electrically to each I/O pin through
a backside via of the integrated circuit.

12. (Original) The method of claim 11, further including:

providing additional I/O pins; and
electrically connecting each additional I/O pin to one frontside I/O pad of the integrated
circuit by a global wiring connection.

13-14. (Canceled)

15. (Currently amended 1) The method of claim [[14]] 11, further including:

providing additional predefined circuit I/O pins; and
electrically connecting each additional I/O pin to one frontside I/O pad of the integrated circuit by a global wiring connection.

16. (Original) The method of claim 11 further including:

forming said backside via in a bulk silicon substrate or a silicon on insulator substrate.

17-22. (Cancelled)

23. (Previously presented) An integrated circuit, comprising:

a predefined block of functional circuitry having a plurality of I/O pins;
a backside I/O pad electrically connected to each I/O pin through a backside via of the integrated circuit;
a semiconductor substrate comprising semiconductor portions of devices;
a device level on the semiconductor substrate and in direct mechanical contact with the semiconductor substrate, wherein the device level includes non-semiconductor portions of said devices;
a first interconnect level on the device level and in direct mechanical contact with the device level; and
a second interconnect level on the first interconnect level and in direct mechanical contact

with the first interconnect level, wherein the predefined block is a core comprising comprises a circuit portion and a redistribution portion, wherein the circuit portion includes all functional circuitry of the core, wherein the circuit portion includes a first portion of the substrate, a first portion of the device layer, a first portion of the first interconnect level, and a first portion of the second interconnect level, wherein the redistribution portion includes a second portion of the substrate, a second portion of the device layer, and a second portion of the first interconnect level, wherein the second portion of the substrate and the second portion of the device layer do not include any device, and wherein the plurality of I/O pins are contained in their entirety within the second portion of the first interconnect level in the redistribution portion.

24. (Previously presented) The integrated circuit of claim 23, wherein the backside via comprises:

a bulk conductor;
a conductor liner circumscribing the bulk conductor and in direct mechanical contact with the bulk conductor, wherein an I/O pin of the plurality of I/O pins is in direct mechanical and electrical contact with the conductor liner; and
an insulating liner circumscribing the conductor liner and in direct mechanical contact with the conductor liner, wherein the insulating liner insulates the bulk conductor from the semiconductor substrate.

25. (Previously presented) An integrated circuit, comprising:

a predefined block of functional circuitry having a plurality of I/O pins; and

a backside I/O pad electrically connected to each I/O pin through a backside via of the integrated circuit, wherein the backside via comprises:

a bulk conductor;

a conductor liner circumscribing the bulk conductor and in direct mechanical contact with the bulk conductor, wherein an I/O pin of the plurality of I/O pins is in direct mechanical and electrical contact with the conductor liner; and

an insulating liner circumscribing the conductor liner and in direct mechanical contact with the conductor liner, wherein the insulating liner insulates the bulk conductor from the semiconductor substrate.

26. (Previously presented) A method of making electrical connection to an integrated circuit, comprising:

providing a predefined block of functional circuitry having a plurality of I/O pins;
connecting a backside I/O pad electrically to each I/O pin through a backside via of the integrated circuit;

providing a semiconductor substrate comprising semiconductor portions of devices;
providing a device level on the semiconductor substrate and in direct mechanical contact with the semiconductor substrate, wherein the device level includes non-semiconductor portions of said devices;

providing a first interconnect level on the device level and in direct mechanical contact with the device level; and

providing a second interconnect level on the first interconnect level and in direct

mechanical contact with the first interconnect level, wherein the predefined block is a core comprising comprises a circuit portion and a redistribution portion, wherein the circuit portion includes all functional circuitry of the core, wherein the circuit portion includes a first portion of the substrate, a first portion of the device layer, a first portion of the first interconnect level, and a first portion of the second interconnect level, wherein the redistribution portion includes a second portion of the substrate, a second portion of the device layer, and a second portion of the first interconnect level, wherein the second portion of the substrate and the second portion of the device layer do not include any device, and wherein the plurality of I/O pins are contained in their entirety within the second portion of the first interconnect level in the redistribution portion.

27. (Previously presented) The integrated circuit of claim 26, wherein the backside via comprises:

 a bulk conductor;
 a conductor liner circumscribing the bulk conductor and in direct mechanical contact with the bulk conductor, wherein an I/O pin of the plurality of I/O pins is in direct mechanical and electrical contact with the conductor liner; and
 an insulating liner circumscribing the conductor liner and in direct mechanical contact with the conductor liner, wherein the insulating liner insulates the bulk conductor from the semiconductor substrate.

28. (Previously presented) A method of making electrical connection to an integrated circuit, comprising:

providing a predefined block of functional circuitry having a plurality of I/O pins; and connecting a backside I/O pad electrically to each I/O pin through a backside via of the integrated circuit, wherein the backside via comprises:

a bulk conductor;

a conductor liner circumscribing the bulk conductor and in direct mechanical contact with the bulk conductor, wherein an I/O pin of the plurality of I/O pins is in direct mechanical and electrical contact with the conductor liner; and

an insulating liner circumscribing the conductor liner and in direct mechanical contact with the conductor liner, wherein the insulating liner insulates the bulk conductor from the semiconductor substrate.

29. (New) The integrated circuit of claim 1, wherein the backside via comprises a sloped sidewall.

30. (New) The integrated circuit of claim 1, wherein a first portion of the backside I/O pad is in direct mechanical contact with the backside via, wherein a second portion of the backside I/O pad is not in direct mechanical contact with the backside via, and wherein the second portion of the backside I/O pad is in direct mechanical contact with a backside surface of the integrated circuit.

31. (New) The integrated circuit of claim 1, wherein the backside via extends through a buried oxide layer (BOX) of the integrated circuit.

32. (New) The method of claim 11, wherein the backside via comprises a sloped sidewall.

33. (New) The method of claim 11, wherein a first portion of the backside I/O pad is in direct mechanical contact with the backside via, wherein a second portion of the backside I/O pad is not in direct mechanical contact with the backside via, and wherein the second portion of the backside I/O pad is in direct mechanical contact with a backside surface of the integrated circuit.

34 (New) The method of claim 11, wherein the backside via extends through a buried oxide layer (BOX) of the integrated circuit.

35. (New) The method of claim 11, wherein said I/O pins are formed in a lowest interconnect level of the integrated circuit.